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APPLICATION N	١٥.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/639,073		08/11/2003	Bohumil Lojek	ATM-250	6954	
3897	7590	04/27/2004		EXAMINER		
	CK & SCH	INECK	HUYNH,	, ANDY		
P.O. BOX 2-E SAN JOSE, CA 95109-0005				ART UNIT	PAPER NUMBER	
	,			2818		
				DATE MAILED, 04/27/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/639,073	LOJEK, BOHUMIL				
Office Action Summary		Examiner	Art Unit				
		Andy Huynh	2818				
Period fo	The MAILING DATE of this communication app		correspondence address				
A SH THE - Exte after - If the - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REPL MAILING DATE OF THIS COMMUNICATION. Insions of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. It is period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period are to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be ti y within the statutory minimum of thirty (30) da will apply and will expire SIX (6) MONTHS fror , cause the application to become ABANDON	mely filed ys will be considered timely. n the mailing date of this communication. ED (35 U.S.C. § 133).				
Status							
1)⊠	Responsive to communication(s) filed on 29 N						
,—	•	s action is non-final.					
3)	3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
	closed in accordance with the practice under l	<u>=x рапе Quayle,</u> 1935 С.D. 11, 4	53 U.G. 213.				
Disposit	ion of Claims						
5)□ 6)⊠	Claim(s) 1-21 is/are pending in the application 4a) Of the above claim(s) 1-4 is/are withdrawn Claim(s) is/are allowed. Claim(s) 5-21 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or	from consideration.					
Applicat	ion Papers						
10)⊠	The specification is objected to by the Examine The drawing(s) filed on 29 March 2004 is/are: Applicant may not request that any objection to the Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Examine The specification is objected to be specification in the specification is objected to be specification in the specification is objected to be specification in the specification in the specification is objected to be specification in the specification in the specification is objected to be specification in the specification in the specification is objected to be specification in the specification in the specification is objected to by the Examine The specification is objected to be specification in the specification in the specification is objected to be specification.	a) accepted or b) objected drawing(s) be held in abeyance. So tion is required if the drawing(s) is o	ee 37 CFR 1.85(a). bjected to. See 37 CFR 1.121(d).				
Priority (under 35 U.S.C. § 119						
12)□ a)	Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document Certified copies of the priority document Copies of the certified copies of the priority document All Copies of the certified copies of the priority document Copies of the certified copies of the priority document Copies of the certified copies of the priority document Copies of the priority document Copies of the certified copies of the priority document Copies of the certified copies of the priority document Copies of the certified copies of the priority document Copies of the Copies of th	ts have been received. ts have been received in Applica nity documents have been receiv u (PCT Rule 17.2(a)).	tion Noved in this National Stage				
	ce of References Cited (PTO-892)	4)					
3) 🛛 Infor	ce of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08 er No(s)/Mail Date 11/24/03.		Patent Application (PTO-152)				

Paper No(s)/Mail Date <u>11/24/03</u>.

DETAILED ACTION

Election/Restrictions

In the Response to the Restriction Requirement dated March 29, 2004, Applicant has elected, without traverse, Group II including claims 5-11, drawn to a device, amended claims 5-11, and added new claims 12-21 is acknowledged. Accordingly, claims 1-4 are withdrawn from consideration as being directed to a non-elected invention. See 37 CFR 35 § 1.142(b) and MPEP § 821.03. Applicant has the right to file a divisional application covering the subject matter of the non-elected claims 1-4, drawn to a method.

Information Disclosure Statement

This office acknowledges receipt of the following items from the applicant: Information Disclosure Statement (IDS) filed on November 24, 2003. The references cited on the PTOL 1449 form have been considered.

Claim Rejections - 35 USC § 112

The following is a quotation of the first paragraph of 35 U.S.C. 112:

The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.

Claims 8, 10, 11, 16, 19, 20 and 21 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled

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in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention.

In claims 8 and 16, "said second layer is oxide" is not disclosed or described in the specification.

In claims 10 and 19, wherein said substrate layer further comprises "a thin surface layer" is not disclosed or described in the specification.

In claims 11 and 20, "an input/output port in communication with said memory array; and a controller coupled to said input/output port and said memory array" is not disclosed or described in the specification.

In claim 21, "an input/output port in communication with said memory array" is not disclosed or described in the specification.

Claim Rejections - 35 U.S.C. § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 5-7 and 13-15 are rejected under 35 U.S.C. 102(b) as being anticipated by Hoang (USP: 6,420,753), Applicant submitted prior art (ASPA).

Regarding claims 5 and 13, Hoang discloses in Fig. 4c and related texts as set forth in column 8, lines 13-36, a block alterable memory cell/a dual transistor non-volatile electrically delectable and alterable semiconductor memory cell, comprising:

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a substrate layer (130) having a source implant/doped region/a source region (136), an active region (a region is laying between doped regions (132) and (134)), a floating gate transistor region/a doped region (134), and a drain implant/doped region/a drain region (132); a tunnel oxide layer/a first insulating layer (144, 146, 148) overlaying a portion of said substrate layer;

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a first layer/a floating gate layer (140) overlaying said tunnel oxide layer/the first insulating layer;

an inter poly layer/a second insulating layer (150) overlaying said first layer/the floating gate layer; and

a second layer/a control gate layer (138) extending over said floating gate transistor region and said active region to an edge of said drain implant/doped region/the drain region (Fig. 4c).

Regarding claims 6 and 14, Hoang discloses the block alterable memory cell/the dual transistor non-volatile electrically delectable and alterable semiconductor memory cell of claim 5 or 13, wherein the said substrate layer is a p-type doped substrate (column 6, lines 58-59).

Regarding claims 7 and 15, Hoang discloses in Fig. 4c the block alterable memory cell/the dual transistor non-volatile electrically delectable and alterable semiconductor memory cell of claim 5, wherein said source implant/doped region/the source region (136, N+), said drain implant region/the drain region (132, N+), and said floating gate transistor region/the doped region (134, N+) are n-type implants/dopants.

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Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 9, 12, 17 and 18 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hoang (USP: 6,420,753), Applicant submitted prior art (ASPA), in view of Ling (USP: 5,811,852).

Hoang discloses the claim limitations except for the block alterable memory cell of claim 5 or 13, wherein said inter poly layer is a nitride layer/an ONO layer. Ling teaches that an oxide-nitride-oxide (ONO) layer is formed between a floating gate and a control gate to provide an improved memory cell structure as set forth in column 2, lines 29-36. It would have been obvious to one of ordinary skill in the art at the time of the invention was made to utilize the teaching of forming an oxide-nitride-oxide (ONO) layer as an inter poly layer between a floating gate and a control gate, as taught by Ling in order to improve the memory cell structure.

Conclusion

A shortened statutory period for response to this action is set to expire 3 (three) months and 0 (zero) day from the day of this letter. Failure to respond within the period for response will cause the application to become abandoned (see M.P.E.P 710.02(b)).

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Any inquiry concerning this communication or earlier communications from the examiner should be directed to Andy Huynh, (571) 272-1781. The examiner can normally be reached on Monday-Friday from 8:30 AM to 5:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on (571) 272-1787. The Fax number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the -status of this application or proceeding should be directed to the receptionist whose phone number is (703) 308-0956.

AH

April 21, 2004

Andy Huynh

andy Muga

Patent Examiner